

Notice of References Cited	Application/Control No. 10/025,414		Applicant(s)/Patent Under Reexamination TSAI ET AL.	
	Examiner Jason Proctor		Art Unit 2123	Page 1 of 1

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*	C	US-6,115,546 A	09-2000	Chevallier et al.	716/5
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*	E	US-5,838,583 A	11-1998	Varadarajan et al.	716/9
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*	G	US-6,637,013	10-2003	Li, Mu-Jing	716/5
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	W	E. Sahouria, Y. Granik, N. Cobb, and O. Touban; "Full-chip Process Simulation for Silicon DRC"; 2000, MSM 2000, pages 1-4			
	X	Frank M Schellenberg, "Resolution Enhancement with OPC/PSM", January 2000, pages 1-16			

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.